

**METHOD OF ENHANCING GATE PATTERNING PROPERTIES
WITH REFLECTIVE HARD MASK**

ABSTRACT OF THE DISCLOSURE

An exemplary method of fabricating an integrated circuit can include depositing a reflective metal material layer over a layer of polysilicon, depositing an anti-reflective coating over the reflective metal material layer, trim etching the anti-reflective coating to form a pattern, etching the reflective metal material layer according to the pattern, and removing portions of the polysilicon layer using the pattern formed from the removed portions of anti-reflective coating.